

WE CLAIM:

1. A method of forming a micro pattern on a substrate, the substrate having a surface with a first area, and a second area spaced apart from the first area, the micro
5 pattern being predetermined to be formed in the first area and not to be formed in the second area, said method comprising the steps of:

(a) forming a first shielding layer on the surface of the substrate, the first shielding layer being
10 configured to cover the second area and to expose the first area;

(b) forming a second shielding layer on the surface of the substrate, the second shielding layer being superimposed on the first shielding layer, and being
15 configured to expose the first area of the substrate, and a portion of the first shielding layer;

(c) etching the first area of the substrate exposed from the second shielding layer to form the micro pattern;

20 (d) removing the second shielding layer from the surface of the substrate and the first shielding layer; and

(e) removing the first shielding layer from the surface of the substrate.

25 2. The method as claimed in Claim 1, wherein step (a) includes the sub-steps of:

(a-1) forming a metal layer on the surface of the

substrate;

(a-2) forming a protecting layer on the metal layer, the protecting layer being configured to expose a first portion of the metal layer corresponding to the first area and to cover a second portion of the metal layer
5 corresponding to the second area;

(a-3) etching the metal layer so as to remove the first portion thereof; and

(a-4) removing the protecting layer from the metal
10 layer so as to form the first shielding layer, the second portion of the metal layer serving as the first shielding layer.

3. The method as claimed in Claim 1, wherein the first shielding layer is made of a material different from the substrate, and the second shielding layer is made
15 of a material different from the substrate and the first shielding layer.

4. The method as claimed in Claim 3, wherein the first shielding layer is a hard mask.

20 5. The method as claimed in Claim 4, wherein the first shielding layer is made of chromium.

6. The method as claimed in Claim 3, wherein the second shielding layer is a photoresist layer.